

Notice of References Cited	Application/Control No. 10/657,149	Applicant(s)/Patent Under Reexamination TAKATA ET AL.	
	Examiner Rosemary E. Ashton	Art Unit 1752	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,479,210	11-2002	Kinoshita et al.	430/270.1
*	B	US-6,753,128	06-2004	Lee et al.	430/270.1
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
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	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	V	Wakisaka, T. et al. Development of Advanced ArF Resist Using Alicyclic Methacrylate Copolymer,SPIE,3999,2000,1088-1099.
	W	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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